

WHAT IS CLAIMED IS:

1. A method of producing a light absorbing pattern film coated article with a transmitted light spectrum distribution corresponding to the pattern of a photomask, wherein a light absorbing film coating solution, containing a silicon oxide raw material, a titanium oxide raw material, which contains titanium oxide microparticles, and a gold microparticle raw material, is coated onto the surface of a substrate, the photomask is positioned on top of said coated film, ultraviolet light is irradiated onto said coated film, and said coated film is thereafter heated.

2. A method of producing a light absorbing pattern film coated article as set forth in Claim 1, wherein said light absorbing film coating solution contains the following as main components at the following weight % of solid components;

said silicon oxide raw material	45 to 93% (as SiO_2),
said titanium oxide raw material	3 to 30% (as TiO_2),
with at least 50 weight % (as TiO_2) of said titanium oxide raw material being titanium oxide microparticles, and	
said gold microparticle raw material	4 to 30% (as Au).

3. A method of producing a light absorbing pattern film coated article as set forth in Claim 2, wherein said light absorbing

film coating solution contains, in addition to said silicon oxide raw material, said titanium oxide raw material, and said gold microparticle raw material, the raw material of at least one oxide selected from a group comprised of cobalt oxide, zirconium oxide, aluminum oxide, iron oxide, bismuth oxide, zinc oxide, tin oxide, indium oxide, antimony oxide, vanadium oxide, chromium oxide, copper oxide, manganese oxide, nickel oxide, cerium oxide, boron oxide, tantalum oxide, tungsten oxide, ytterbium oxide at a total content as Co_3O_4 , ZrO_2 , Al_2O_3 , Fe_2O_3 , Bi_2O_3 , ZnO , SnO_2 , In_2O_3 , Sb_2O_3 , V_2O_5 , Cr_2O_3 , CuO , MnO , NiO , Ce_2O_3 , B_2O_3 , Ta_2O_5 , WO_3 , and Yb_2O_3 , respectively, of 15 weight % or less.

4. A method of producing a light absorbing pattern film coated article as set forth in any of Claims 1 through 3, wherein said photomask has a pattern comprised of microscopic ultraviolet ray transmitting regions and microscopic ultraviolet ray blocking regions.

5. A method of producing a light absorbing pattern film coated article as set forth in any of Claims 1 through 4, wherein said titanium oxide microparticles have an average particle diameter of 100nm or less.

6. A method of producing a light absorbing pattern film coated article as set forth in any of Claims 1 through 5, wherein said substrate is comprised of glass, ceramic, or resin.

